

## David L. Windt

### Education

1987 Ph.D., Physics University of Colorado, Boulder  
1985 M.S., Physics University of Colorado, Boulder  
1982 B.S., Physics University of Connecticut, Storrs; *magna cum laude*, *Phi Beta Kappa*

### Professional Experience

2005 – present Founder and President, Reflective X-ray Optics LLC, New York, New York  
2006 – present Adjunct Research Scientist, Columbia Astrophysics Laboratory, New York, New York  
2000 – 2005 Research Scientist, Columbia Astrophysics Laboratory, New York, New York  
1990 – 1999 Member of Technical Staff, Bell Labs, Lucent Technologies, Murray Hill, New Jersey  
1998 Visiting Scholar, Dept. of Physics, New York University, New York  
1989 Resident Visitor, AT&T Bell Laboratories, Murray Hill, New Jersey  
1987 – 1989 Associate Research Scientist, Space Sciences Department, Lockheed Palo Alto Research Laboratory, Palo Alto, California  
1982 – 1987 Graduate Research Assistant, Dept. of Physics, Laboratory for Atmospheric & Space Physics and Center for Astrophysics & Space Astronomy, University of Colorado, Boulder  
1983 Teaching Assistant, Dept. of Physics, University of Colorado, Boulder  
1982 Teaching Assistant, Dept. of Mechanical Engineering, University of Connecticut, Storrs

### Professional Affiliations

- American Astronomical Society
- American Physical Society
- Materials Research Society
- Optical Society of America
- Society of Photo-optical Instrumentation Engineers

### Conference Organization

- Co-founder and co-organizer of the International Conference on the Physics of X-ray Multilayer Structures (PXRMS), held biennially from 1992 through 2010
- Co-organizer of the US-Japan workshop on EUV lithography, 1993

### Patents

7 patents relating to multilayer and thin-film technology with applications to photolithography, film deposition, and medical imaging.

### Publications

Numerous technical publications on thin films and multilayer coatings, X-ray astronomy, X-ray lithography and X-ray mammography. Two software packages in wide use among the scientific community: IMD – for modeling and fitting specular and non-specular multilayer optical properties, and TOPO – for surface topography analysis.